***Linear, third order nonlinear and optical limiting studies on MZO/FTO thin films system fabricated by spin coating technique for electro-optic applications***

***Mohd. Shkir1, Mohd. Arif2, V. Ganesh1, M.A. Manthrammel1, Arun Singh2, S.R. Maidur3, P.S. Patil3, I.S. Yahia1, H. Algarni1, S. AlFaify\*1***

*1Advanced Functional Materials and Optoelectronics Laboratory (AFMOL),* *Department of Physics, College of Science, King Khalid University, Abha 61413, P.O. Box 9004, Saudi Arabia.*

*2Department of Physics, Jamia Millia Islamia (a central university), New Delhi 110025 India.*

*3Department of Engineering Physics, K. L. E. Institute of Technology, Opposite Airport, Gokul, Hubballi 580030, India*

FIG. S1 EDAX elemental mapping image for 5% Mg doped ZnO film

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FIG. S2 (a) ε1 (b) ε2, (c) SELF and (d) VELF plots for deposited films

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